

FIG. Z

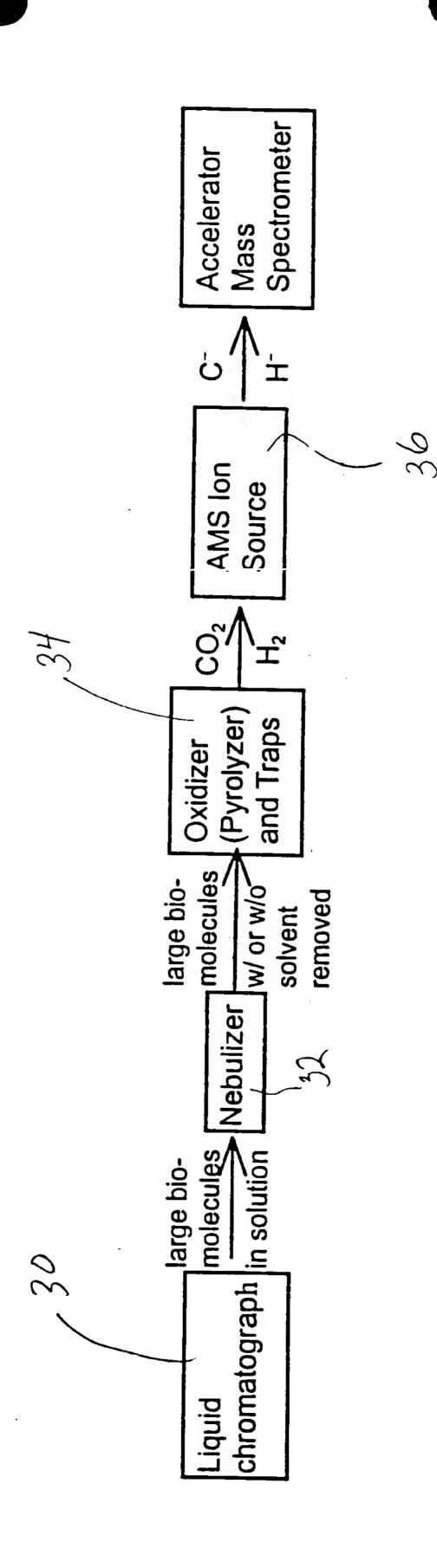


FIG. 5

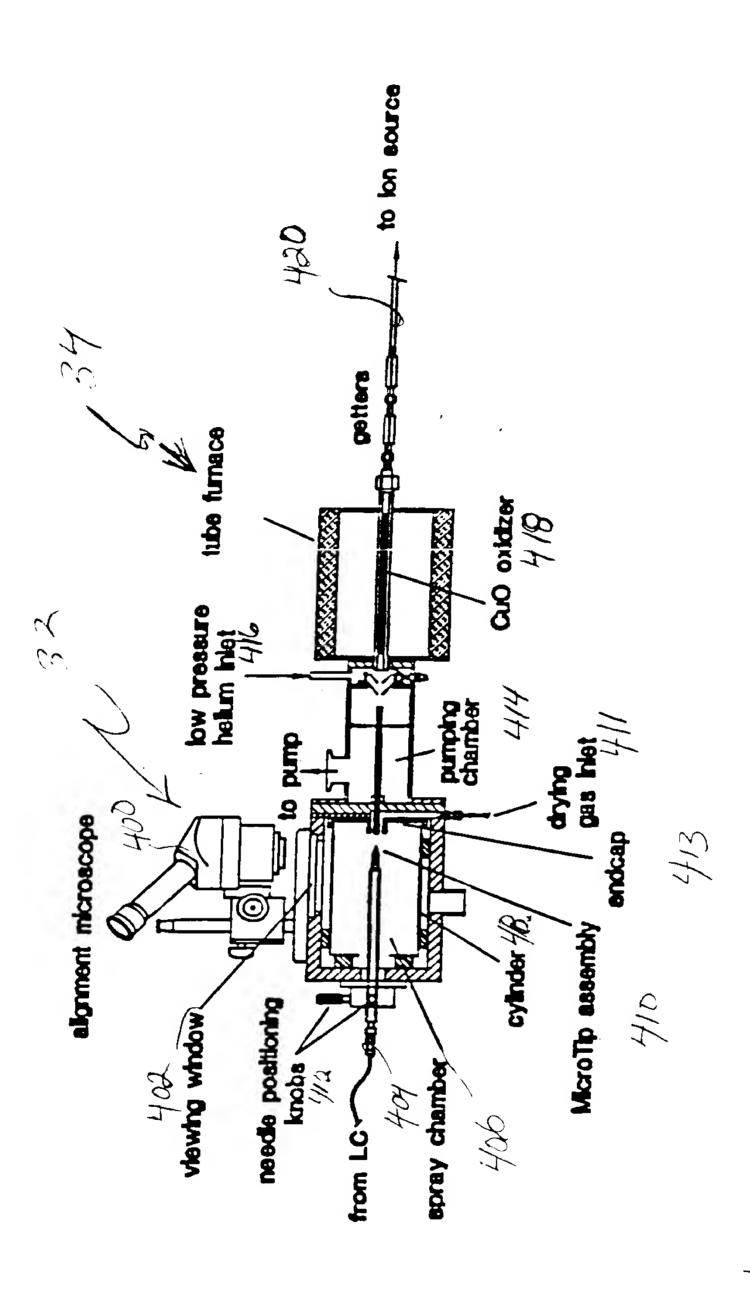


FIG. 4H

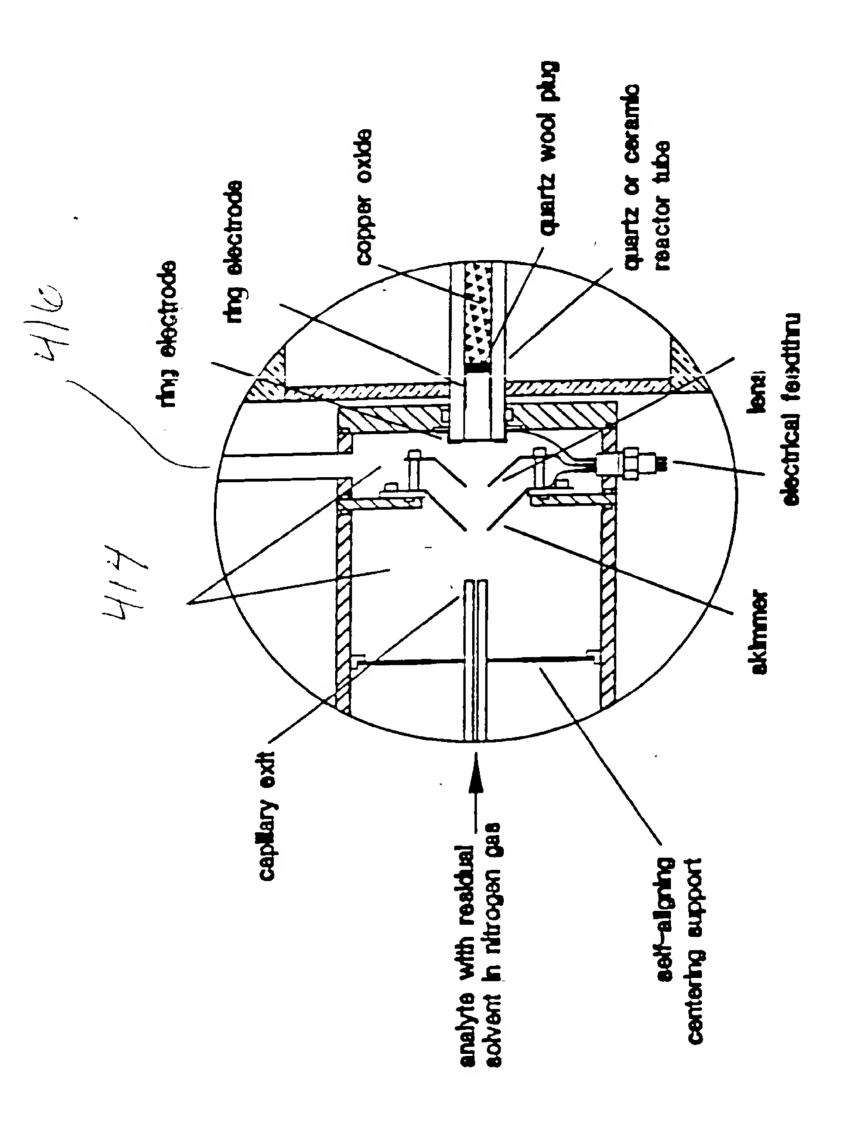


FIG. 418

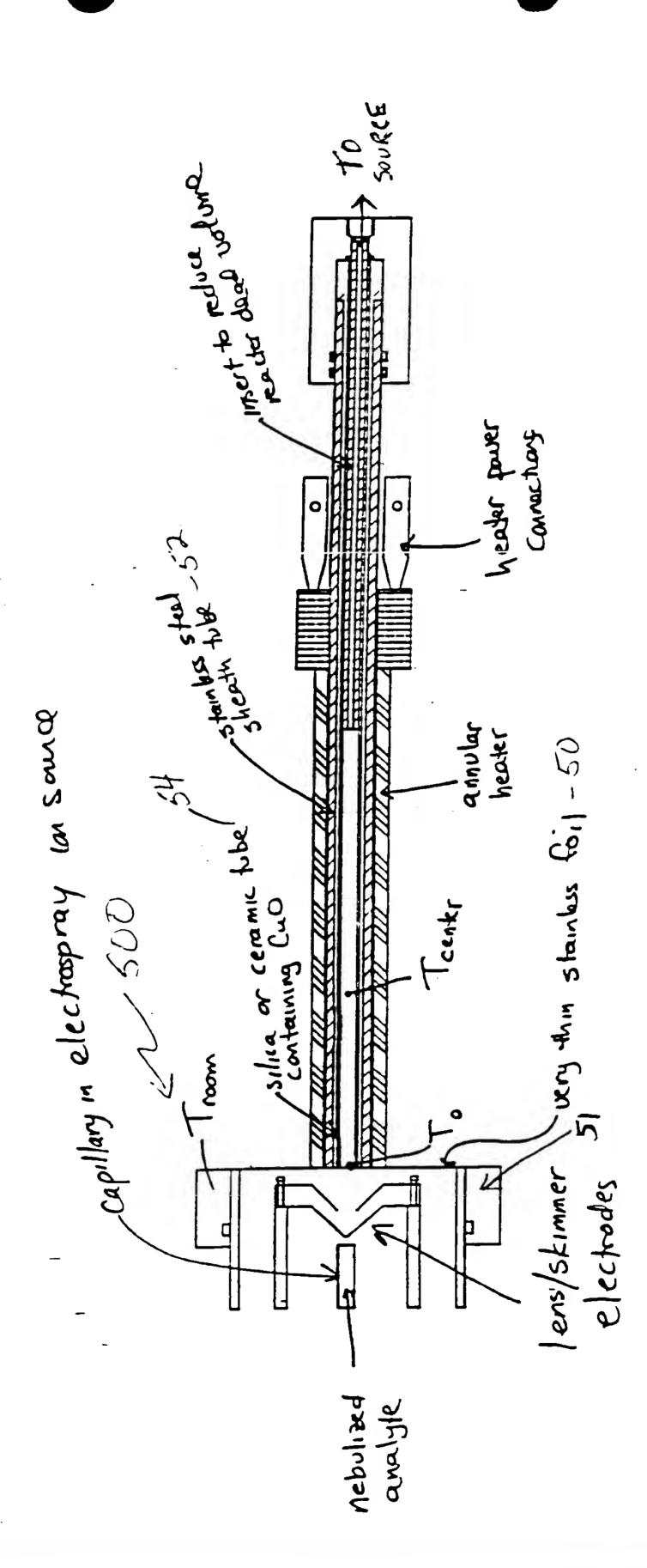
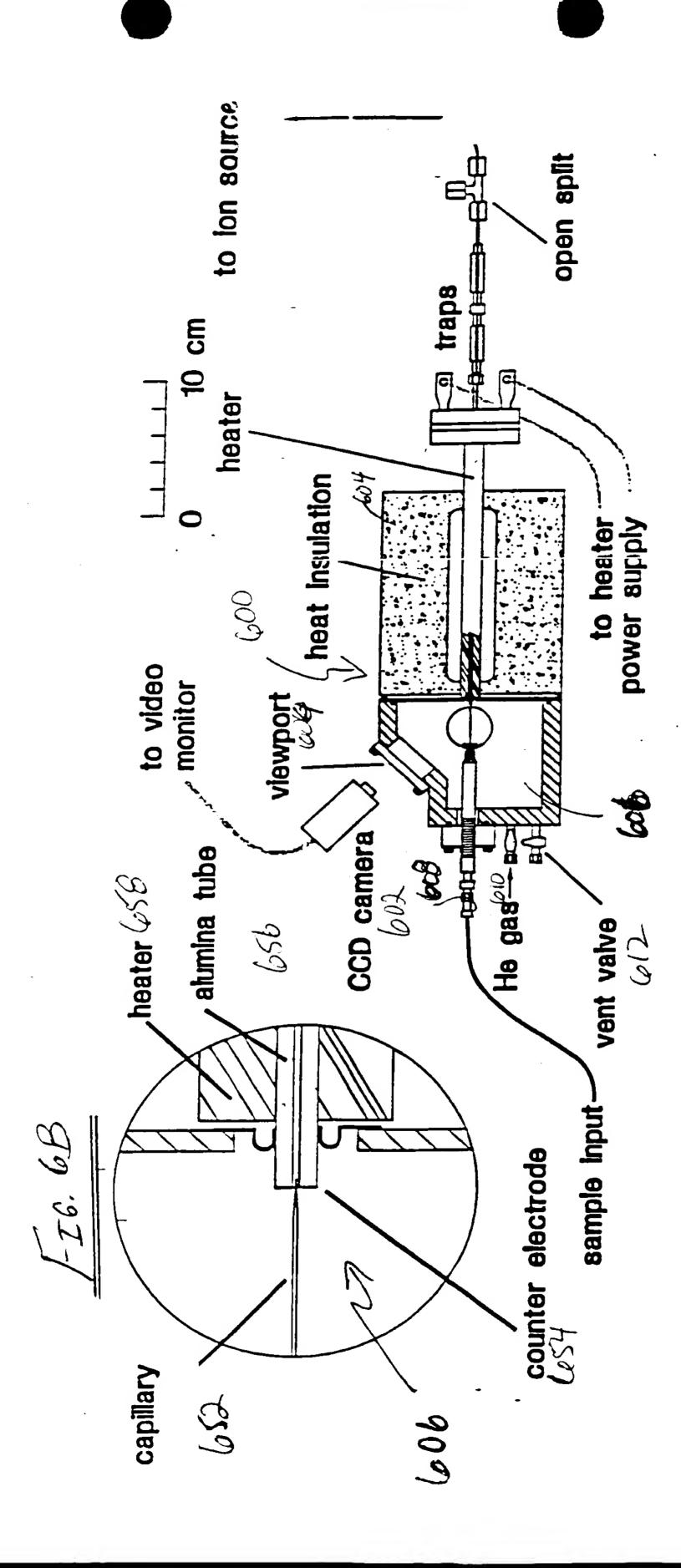
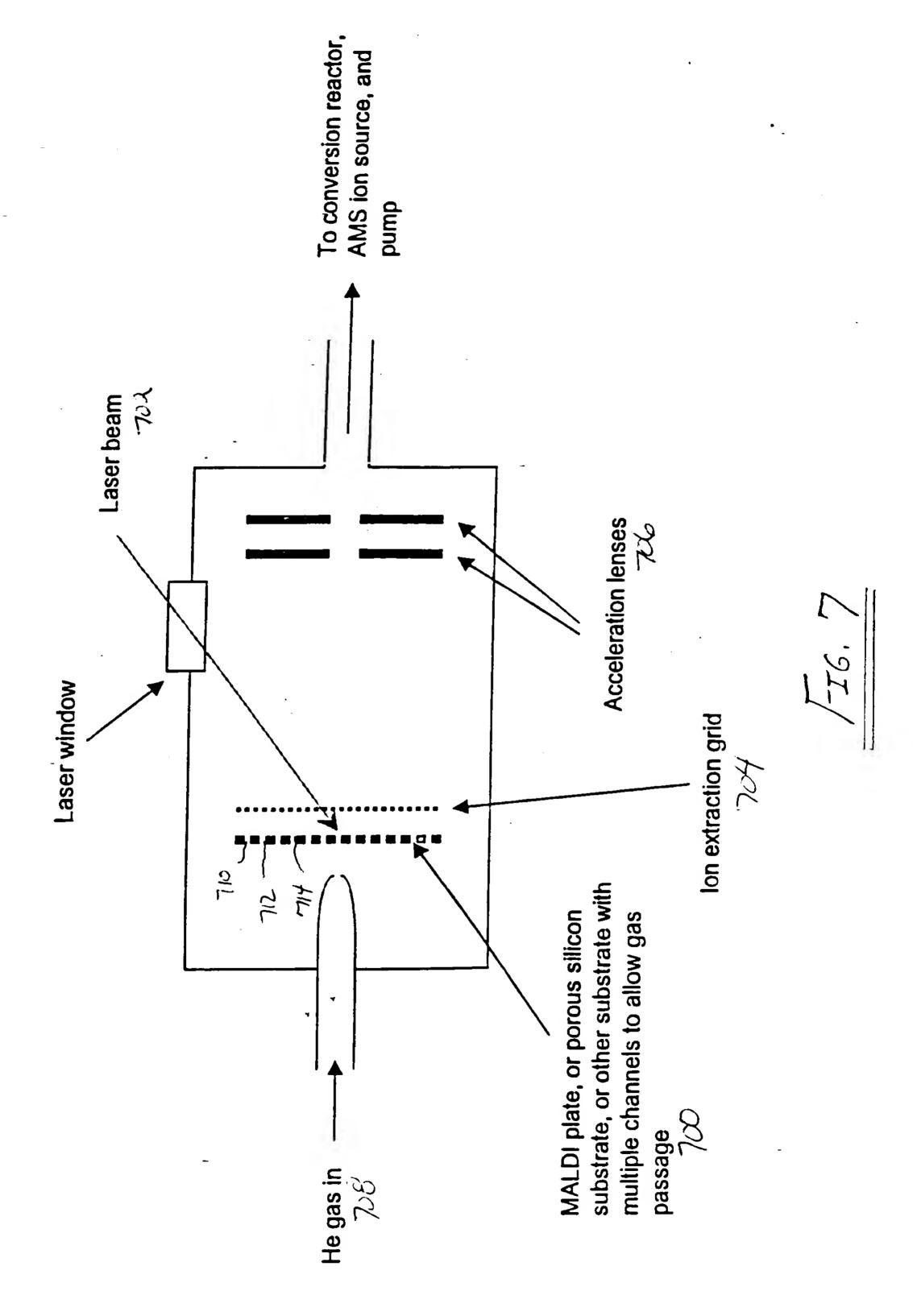
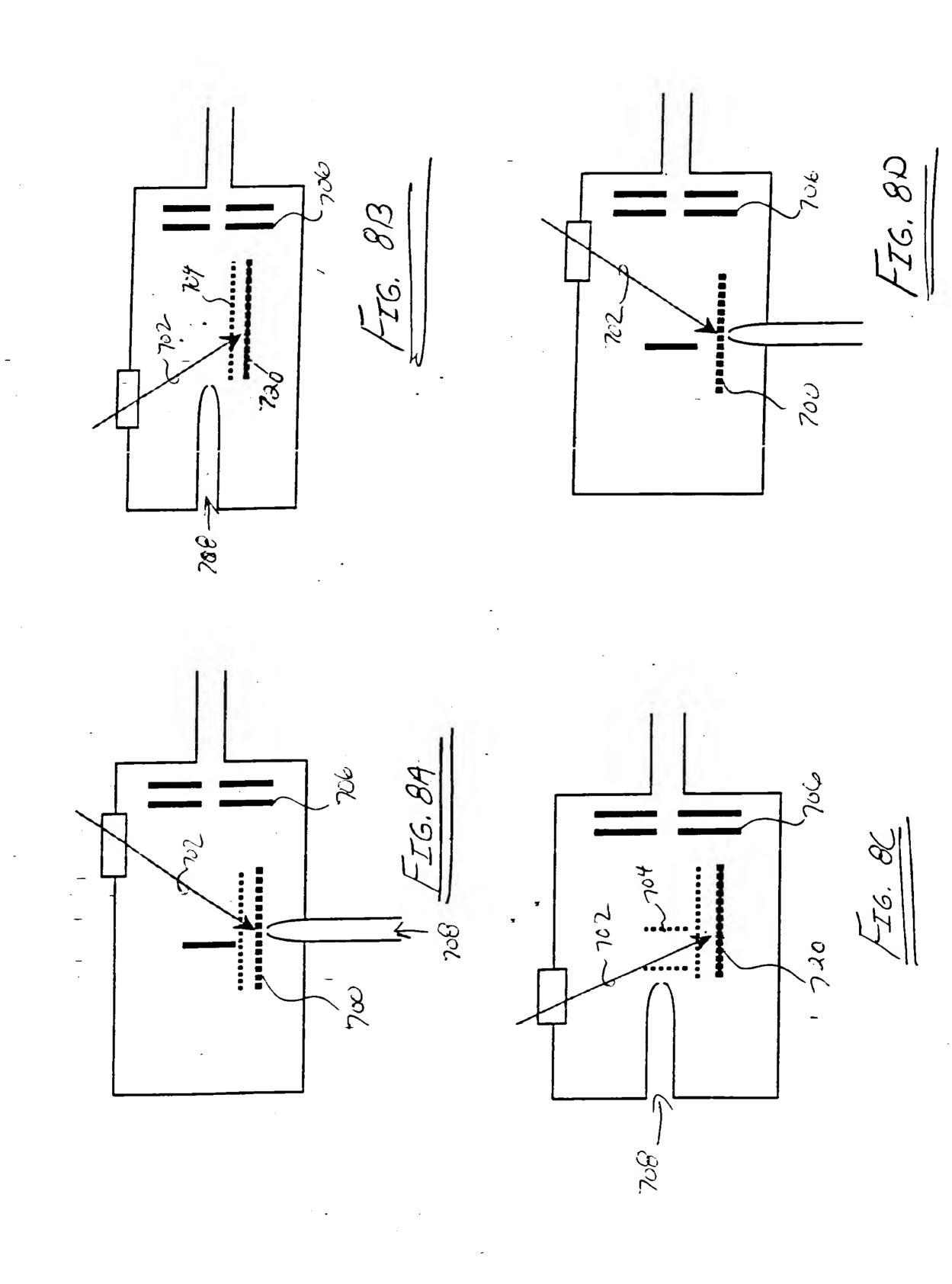


FIG. 5



FIE. 6A





Laser beam Sample dispensing Sample input GCG apparatus substrate Converted 400 404 chemical form Sample bed 904 Sample applied Sweep gas in to sample bed Laser-induced conversion Sample deposition Laser beam Sample input CO₂ in He Pipetter (e.g. HPLC eluent) to AMS ion source Refractory substrate or other apparatus ,1000 1004 1010 Thin layer of -CuO catalyst 10-2 Sample applied – He gas in to CuO bed Laser-induced combustion Sample deposition F-IC. 1013

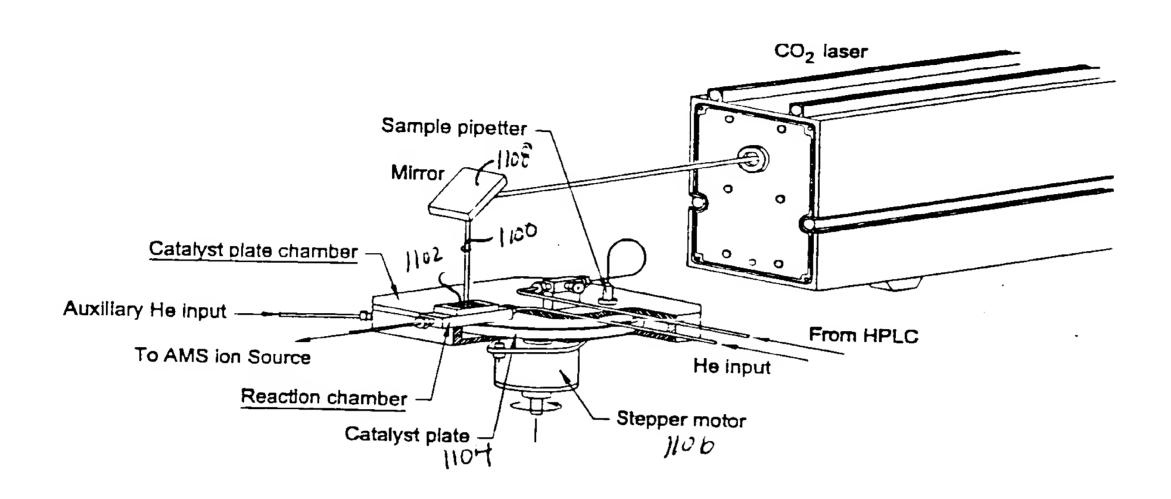
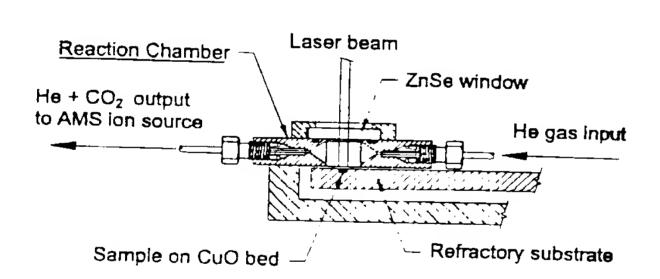


FIG. 1/A



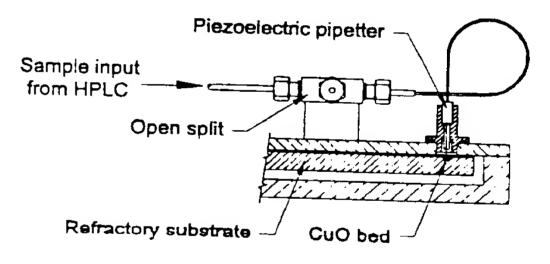


FIG. 11C

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FIG. 118

Pipetter (e.g. HPLC eluent)

Refractory substrate

Thin layer of carbon

Sample applied to carbon bed

Sample deposition

FIG. 12/-

Sample dispensing apparatus

1304

Refractory substrate

300

1300

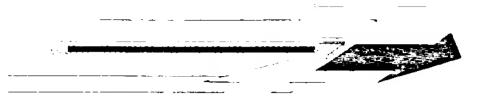
Sample applied to sample bed

Sample deposition

FIG. 13A

Laser beam

H₂ in He to AMS ion source or other apparatus



He gas in

Laser-induced pyrolysis

FIG. 12B

Energy source

C- or H
310

Conversion in ion source

FIG. 13B

Pipetter - Sample input (e.g. HPLC eluent)

Refractory substrate
1402

Sample applied to sample bed

Sample deposition

FIG. 14A

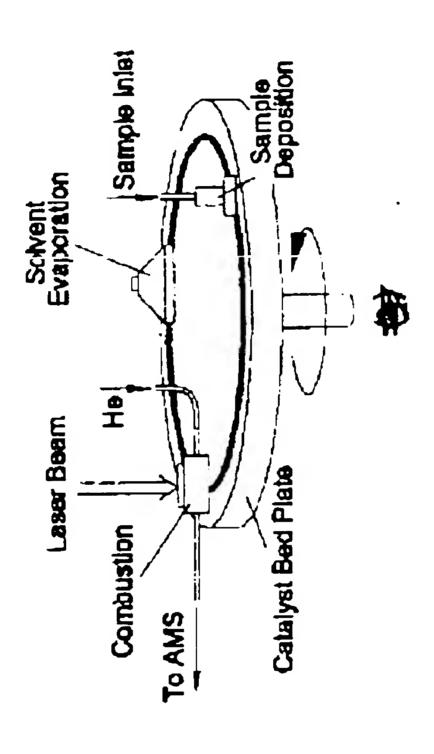
Cs ion beam

1404

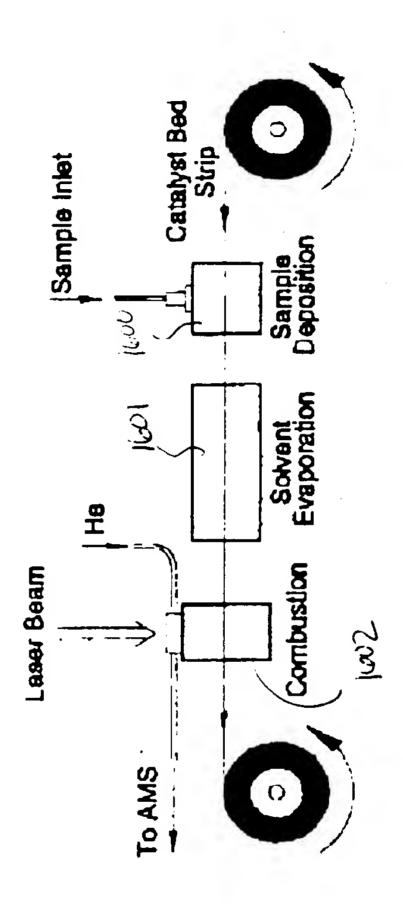
C- or H-1406

Conversion in ion source

FIG. 143



/IG. 15



16.16